


TRANSMITTAL

Electronic Version v1.1

Stylesheet Version v1.1.0

Title of Invention	Methods for the optimization of substrate etching in a plasma processing system					
Application Number : Date : First Named Applicant: Confirmation Number: Attorney Docket Number:	10/804430 2004-03-19 Kim Jisoo 7228 LMRX-P032/P1205					
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Submitted By: Mr. Joseph Nguyen Registered Number: 37899		<table border="1"><thead><tr><th data-bbox="492 629 709 658">Elec. Sign.</th><th data-bbox="709 629 932 658">Sign. Capacity</th></tr></thead><tbody><tr><td data-bbox="492 658 709 704">/jan/</td><td data-bbox="709 658 932 704">Attorney</td></tr></tbody></table>	Elec. Sign.	Sign. Capacity	/jan/	Attorney
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Documents being submitted:	Files
us-ids	LMRX-P032-usidst.xml us-ids.dtd us-ids.xsl
Comments	